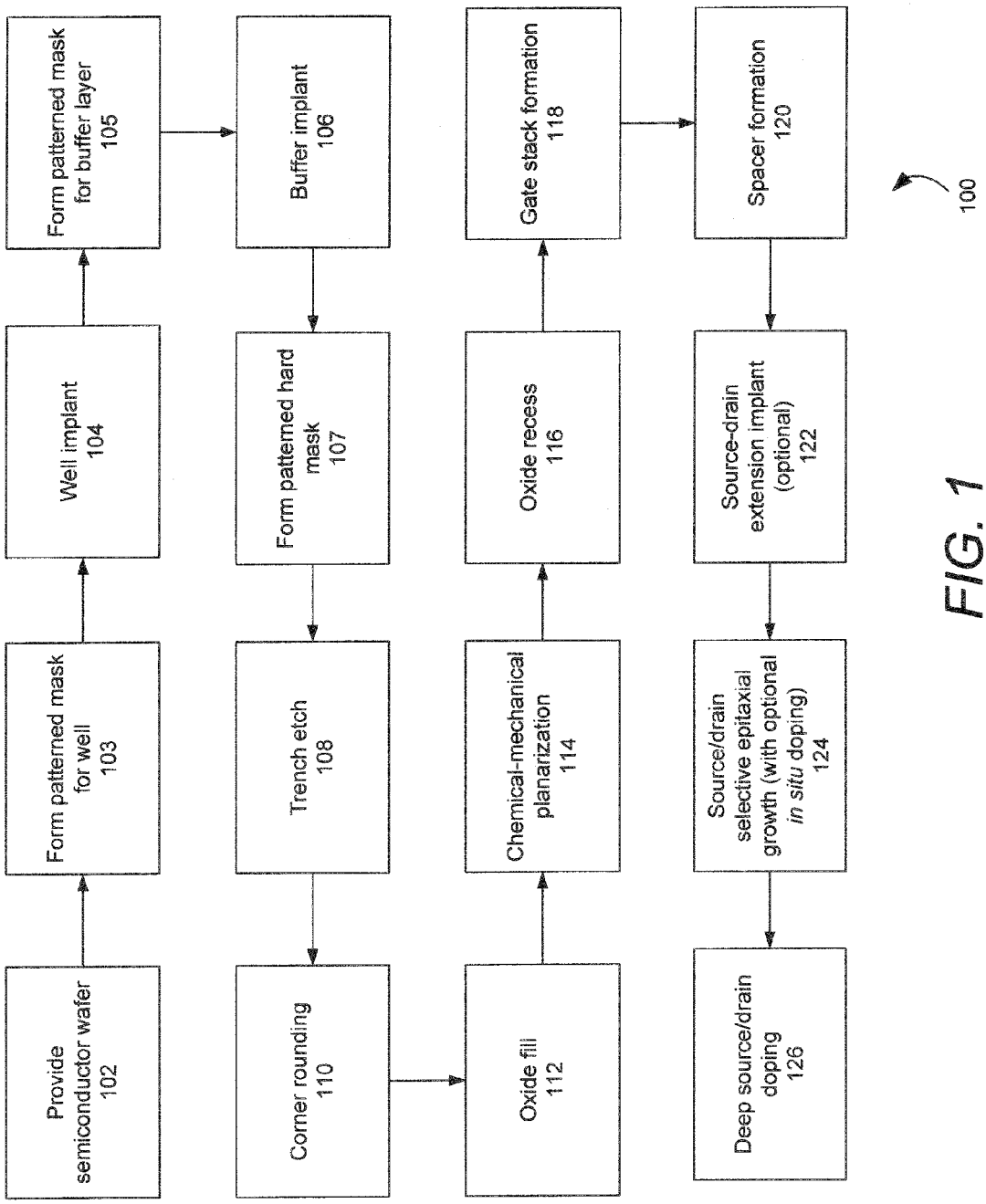
Provide semiconductor wafer 102
Form patterned mask for well 103
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Form patterned hard mask 107
Trench etch 108
Corner rounding 110
Oxide fill 112
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Spacer formation 120
Source-drain extension implant (optional) 122
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Deep source/drain doping 126
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FIG. 1